

WEST Search History

DATE: Tuesday, July 29, 2003

| <u>Set Name</u> side by side | <u>Query</u> | <u>Hit Count</u> | <u>Set Name</u> result set |
|---|--|------------------|-------------------------------|
| <i>DB=USPT,PGPB,JPAB,EPAB,DWPI,TDBD; THES=ASSIGNEE; PLUR=YES; OP=OR</i> | | | |
| L33 | L32 and (plasma adj1 etching) | 3 | L33 |
| L32 | (metal adj1 substrate adj1 cleaning) | 24 | L32 |
| L31 | l17 same (plasma adj1 etching) | 4 | L31 |
| L30 | surface adj1 treatment adj1 metallic adj1 tube | 1 | L30 |
| L29 | L28 with (plasma adj1 etching) | 16 | L29 |
| L28 | (polymer adj1 substrate) | 9187 | L28 |
| L27 | (polymer adj1 subatrate) | 0 | L27 |
| L26 | L25 same (prior adj1 coating) | 2 | L26 |
| L25 | (plasma adj1 etching) same polymer | 1822 | L25 |
| L24 | L23 and photoresist | 39 | L24 |
| L23 | L22 and coating | 80 | L23 |
| L22 | l19 same (plasma adj1 etching) | 140 | L22 |
| L21 | L20 same (prior adj1 coating) | 20 | L21 |
| L20 | L19 same etching | 3802 | L20 |
| L19 | metal adj1 (substrate or surface) | 94827 | L19 |
| L18 | L17 same etching same (prior adj1 coating) | 0 | L18 |
| L17 | (metal adj1 tube) | 28288 | L17 |
| L16 | L15 same (plasma adj1 etching) | 14 | L16 |
| L15 | stent | 15672 | L15 |
| L14 | l13 same photoresist | 33 | L14 |
| L13 | etching same (prior adj coating) | 262 | L13 |
| L12 | l11 same (prior adj coating) | 0 | L12 |
| L11 | l1 same (metal adj1 substrate) | 71 | L11 |
| L10 | L9 | 26 | L10 |
| L9 | l7 and (metal adj substrate) | 26 | L9 |
| L8 | l7 and metal | 75 | L8 |
| L7 | l1 and (prior adj coating) and photoresist | 80 | L7 |
| L6 | l5 and photoresist | 3 | L6 |
| L5 | l3 and metal | 16 | L5 |
| L4 | L3 same tube | 0 | L4 |
| L3 | L2 same (prior adj coating) | 20 | L3 |

| | | | |
|----|-----------------------------|-------|----|
| L3 | L2 same (prior adj coating) | 20 | L3 |
| L2 | plasma adj1 etching | 28106 | L2 |
| L1 | plasma adj1 etching | 28106 | L1 |

END OF SEARCH HISTORY

WEST

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L23: Entry 78 of 80

File: DWPI

Jun 25, 1997

DERWENT-ACC-NO: 1997-322157

DERWENT-WEEK: 200107

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TITLE: Cleaning metal substrate by plasma etching - comprises creating plasma of radicals or ions of hydrogen or inert gas to react with substrate surface negatively biased relatively to anode

INVENTOR: LUCAS, S; VANDEN, B P ; WEYMEERSCH, A ; VANDEN BRANDE, P

PATENT-ASSIGNEE:

ASSIGNEE

CODE

RD-CS RECH & DEV GRP COCKERILL SAMBRE

COCK

PRIORITY-DATA: 1995BE-0001053 (December 20, 1995)

PATENT-FAMILY:

| PUB-NO | PUB-DATE | LANGUAGE | PAGES | MAIN-IPC |
|---------------|-----------------|----------|-------|------------|
| EP 780485 A1 | June 25, 1997 | F | 010 | C23C014/02 |
| ES 2151633 T3 | January 1, 2001 | | 000 | C23C014/02 |
| BE 1009839 A3 | October 7, 1997 | | 015 | C23C000/00 |
| EP 780485 B1 | August 30, 2000 | F | 000 | C23C014/02 |
| DE 69610064 E | October 5, 2000 | | 000 | C23C014/02 |

DESIGNATED-STATES: AT BE CH DE DK ES FI FR GB GR IE IT LI LU NL PT SE AL AT BE CH DE DK
ES FI FR GB GR IE IT LI LT LU LV NL PT RO SE SI

CITED-DOCUMENTS: 2.Jnl.Ref; DD 136047 ; EP 535568

APPLICATION-DATA:

| PUB-NO | APPL-DATE | APPL-NO | DESCRIPTOR |
|--------------|-------------------|----------------|------------|
| EP 780485A1 | December 17, 1996 | 1996EP-0203581 | |
| ES 2151633T3 | December 17, 1996 | 1996EP-0203581 | |
| ES 2151633T3 | | EP 780485 | Based on |
| BE 1009839A3 | December 20, 1995 | 1995BE-0001053 | |
| EP 780485B1 | December 17, 1996 | 1996EP-0203581 | |
| DE 69610064E | December 17, 1996 | 1996DE-0610064 | |
| DE 69610064E | December 17, 1996 | 1996EP-0203581 | |
| DE 69610064E | | EP 780485 | Based on |

INT-CL (IPC): C23 C 0/00; C23 C 14/02; C23 C 16/02; C23 G 5/00

ABSTRACTED-PUB-NO: EP 780485A

BASIC-ABSTRACT:

A metal substrate cleaning process comprises: creating a plasma in a mixture of hydrogen, hydrogen compounds and/or inert gas (e.g. argon) to generate radicals and/or ions for acting on the substrate which is negatively biased with respect to an anode facing the surface to be cleaned. Also claimed is a metal substrate cleaning apparatus, especially for carrying out the above process, comprising devices for generating a plasma and negatively biasing the substrate surface.

USE - Used for metal surfaces, especially steel strips, to enhance adhesion of a subsequent coating, e.g. an electroplated or hot dip coating.

ADVANTAGE - The process eliminates the handling and regeneration problems of pickling solutions, and is carried out continuously at high speed and very efficiently.

ABSTRACTED-PUB-NO:

EP 780485B

EQUIVALENT-ABSTRACTS:

A metal substrate cleaning process comprises: creating a plasma in a mixture of hydrogen, hydrogen compounds and/or inert gas (e.g. argon) to generate radicals and/or ions for acting on the substrate which is negatively biased with respect to an anode facing the surface to be cleaned. Also claimed is a metal substrate cleaning apparatus, especially for carrying out the above process, comprising devices for generating a plasma and negatively biasing the substrate surface.

USE - Used for metal surfaces, especially steel strips, to enhance adhesion of a subsequent coating, e.g. an electroplated or hot dip coating.

ADVANTAGE - The process eliminates the handling and regeneration problems of pickling solutions, and is carried out continuously at high speed and very efficiently.

CHOSEN-DRAWING: Dwg.3/3

TITLE-TERMS: CLEAN METAL SUBSTRATE PLASMA ETCH COMPRISE PLASMA RADICAL ION HYDROGEN
INERT GAS REACT SUBSTRATE SURFACE NEGATIVE BIAS RELATIVELY ANODE

DERWENT-CLASS: M12 M14 X25

CPI-CODES: M12-A05; M14-A;

EPI-CODES: X25-A04;

SECONDARY-ACC-NO:

CPI Secondary Accession Numbers: C1997-104256

Non-CPI Secondary Accession Numbers: N1997-266538